Abstract of the Disclosure

A semiconductor memory device including 1T-1C memory cells for increasing an access speed thereto. The semiconductor memory device is composed of a substrate, a MOS (metal oxide

- 5 semiconductor) transistor formed in a surface portion of the substrate, an inter-level dielectric covering the MOS transistor, a capacitor element, and a contact formed through the inter-level dielectric. The contact
- 10 electrically connects the capacitor element to
 the MOS transistor on a source thereof. The
 contact includes a metal portion formed of metal.
 The metal portion reduces the resistance of the
 contact, and thereby increases the access speed
- 15 of the semiconductor memory device.